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**Ker et al.**

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(54) **TURN-ON-EFFICIENT BIPOLAR  
STRUCTURES WITH DEEP N-WELL FOR  
ON-CHIP ESD PROTECTION**

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17, 2003.

(51) **Int. Cl.**  
**H01L 23/62** (2006.01)

(52) **U.S. Cl.** ..... **257/355; 257/362; 257/E21.061;**  
**257/E27.063**

(58) **Field of Classification Search** ..... **257/355,**  
**257/361**

See application file for complete search history.

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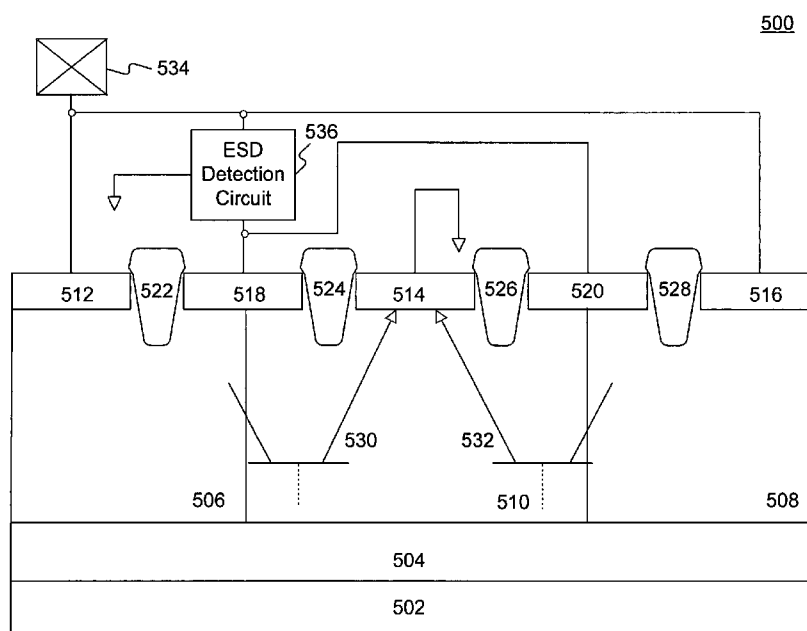
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(57) **ABSTRACT**

A semiconductor device suitable for applications in an  
electrostatic discharge (ESD) protection circuit, including a  
semiconductor substrate, a first well formed in the substrate,  
a second well formed in the substrate, and a first doped  
region formed in the second well, wherein the first well, the  
second well, and the first doped region collectively form a  
parasitic bipolar junction transistor (BJT), and wherein the  
first well is the collector of the BJT, the second well is the  
base of the BJT, and the first doped region is the emitter of  
the BJT.

**44 Claims, 14 Drawing Sheets**



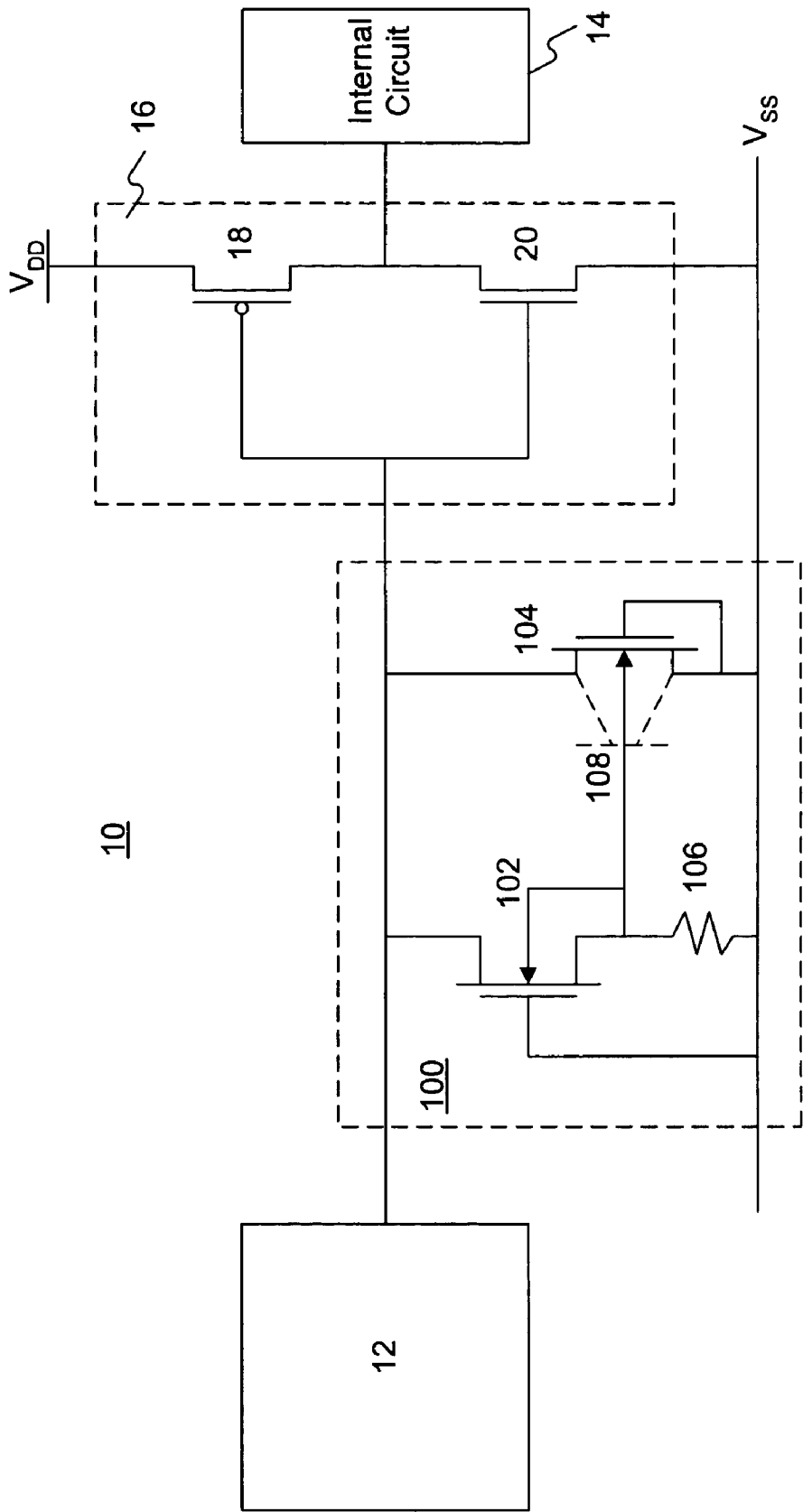
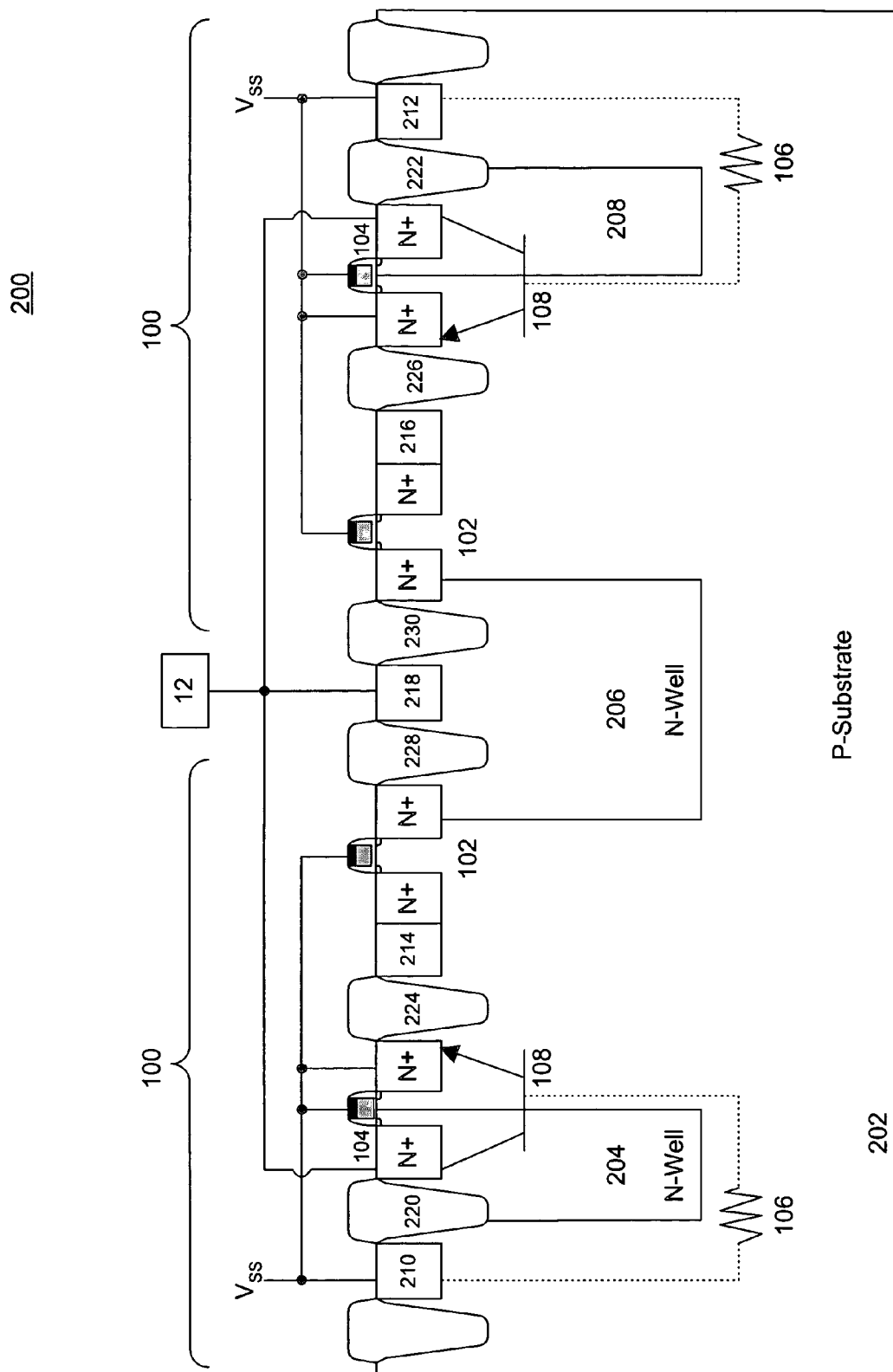
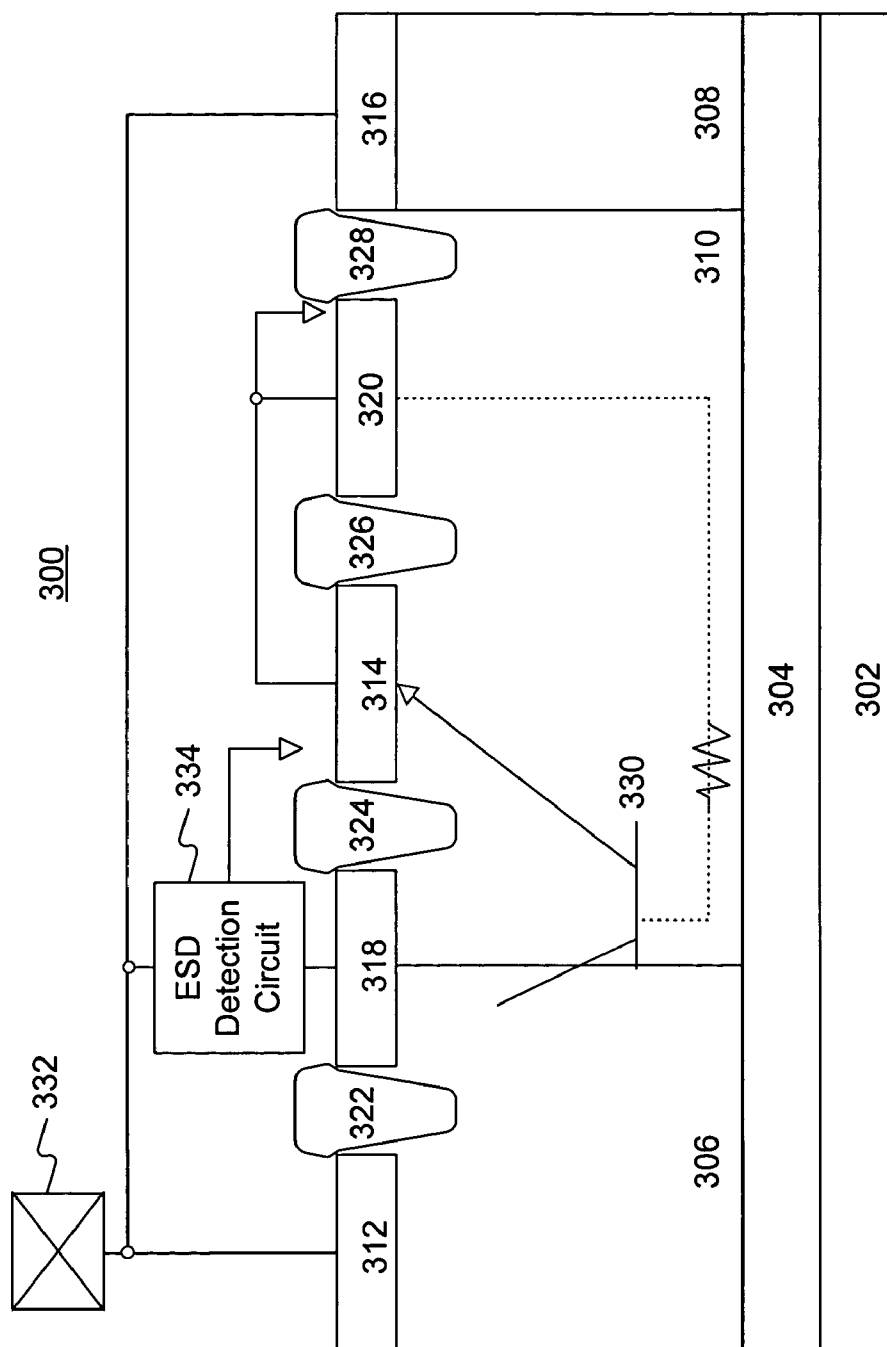


Fig. 1  
Prior Art



**Fig. 2**  
**Prior Art**



39

400

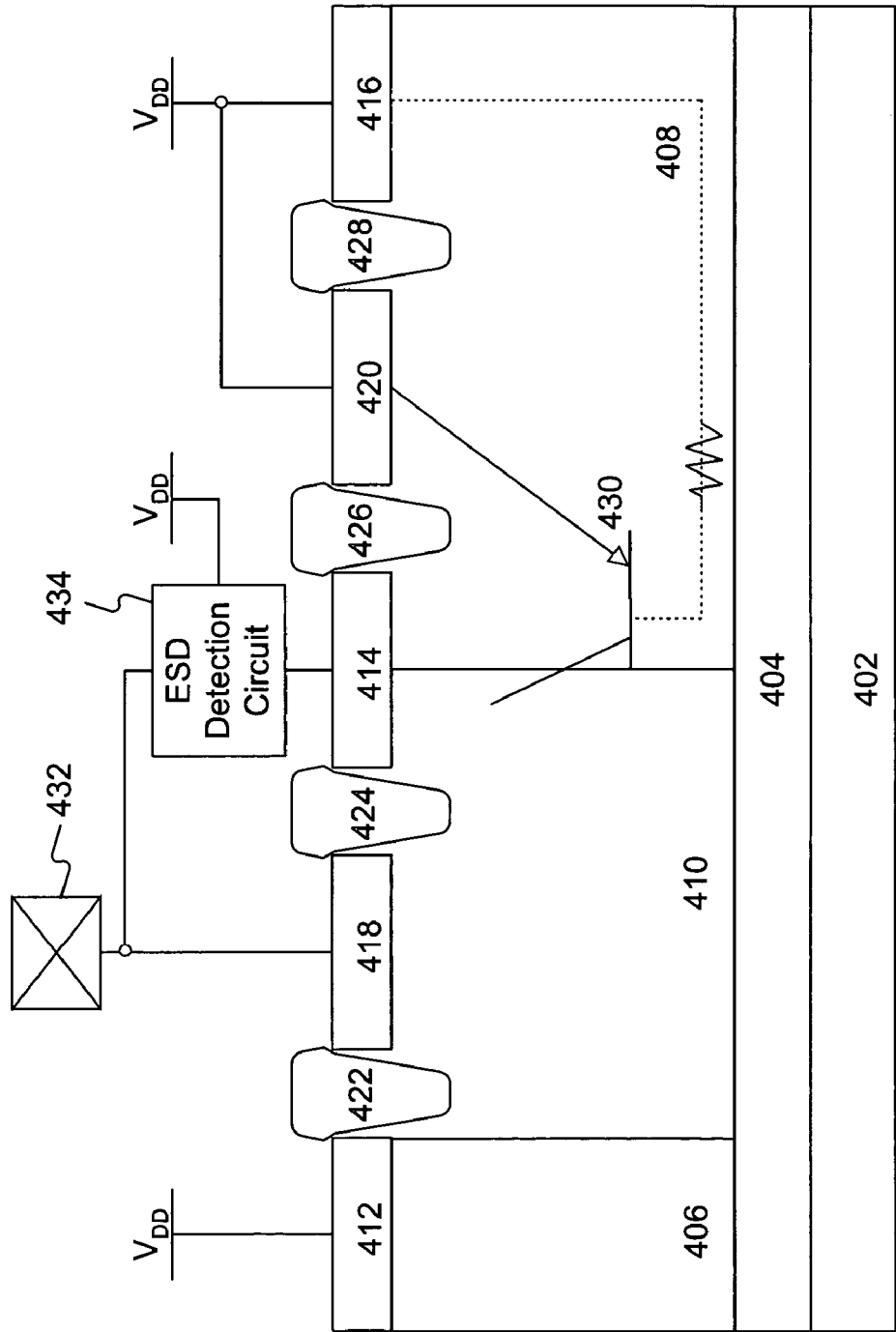


Fig. 4

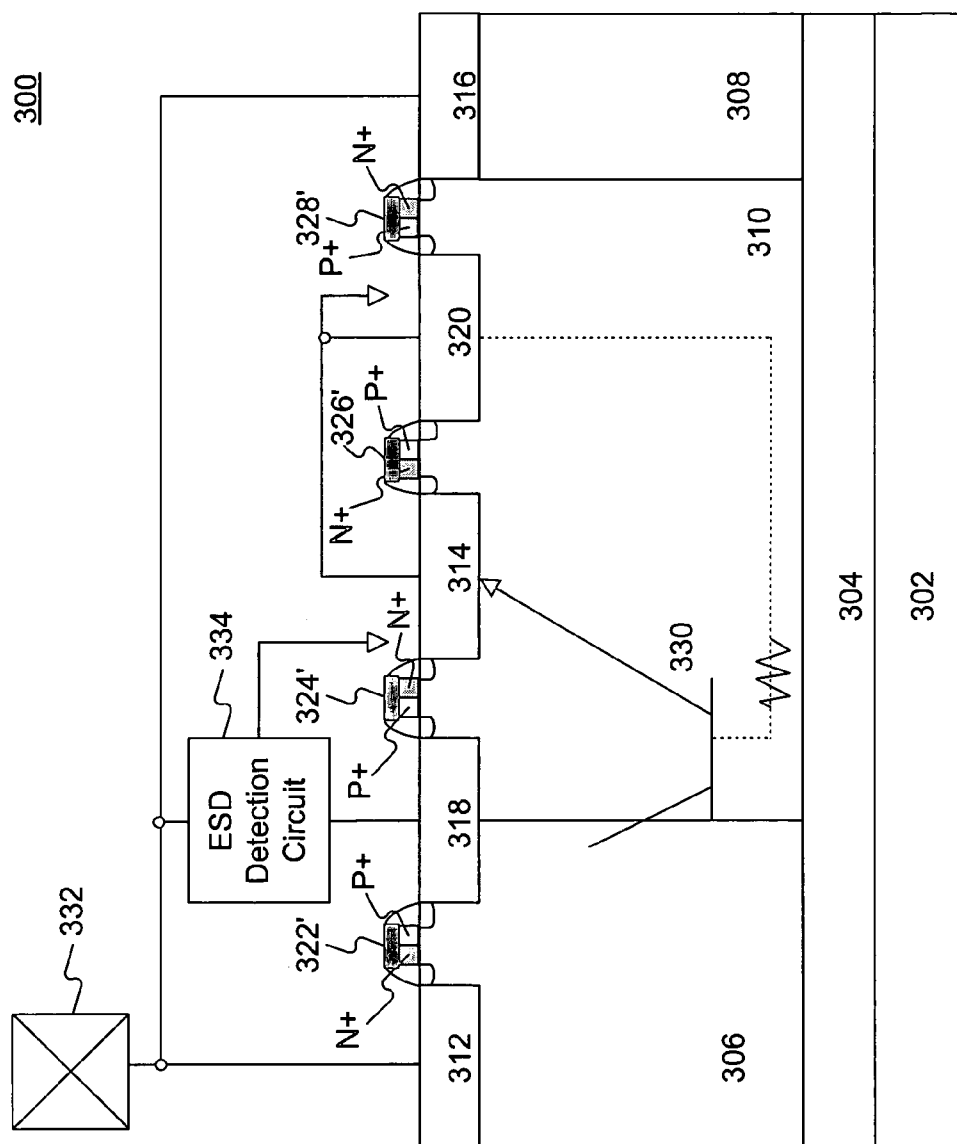
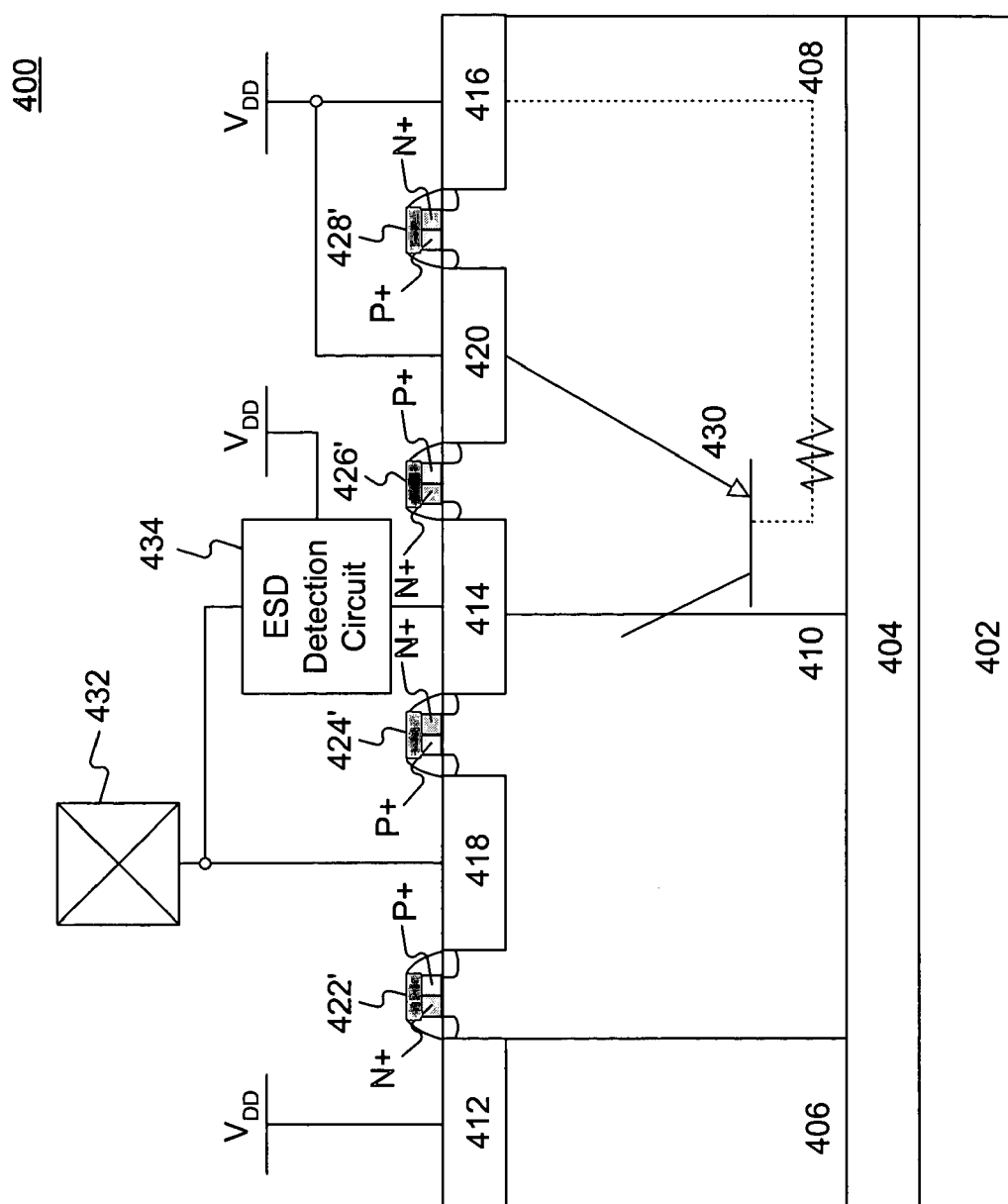


Fig. 5



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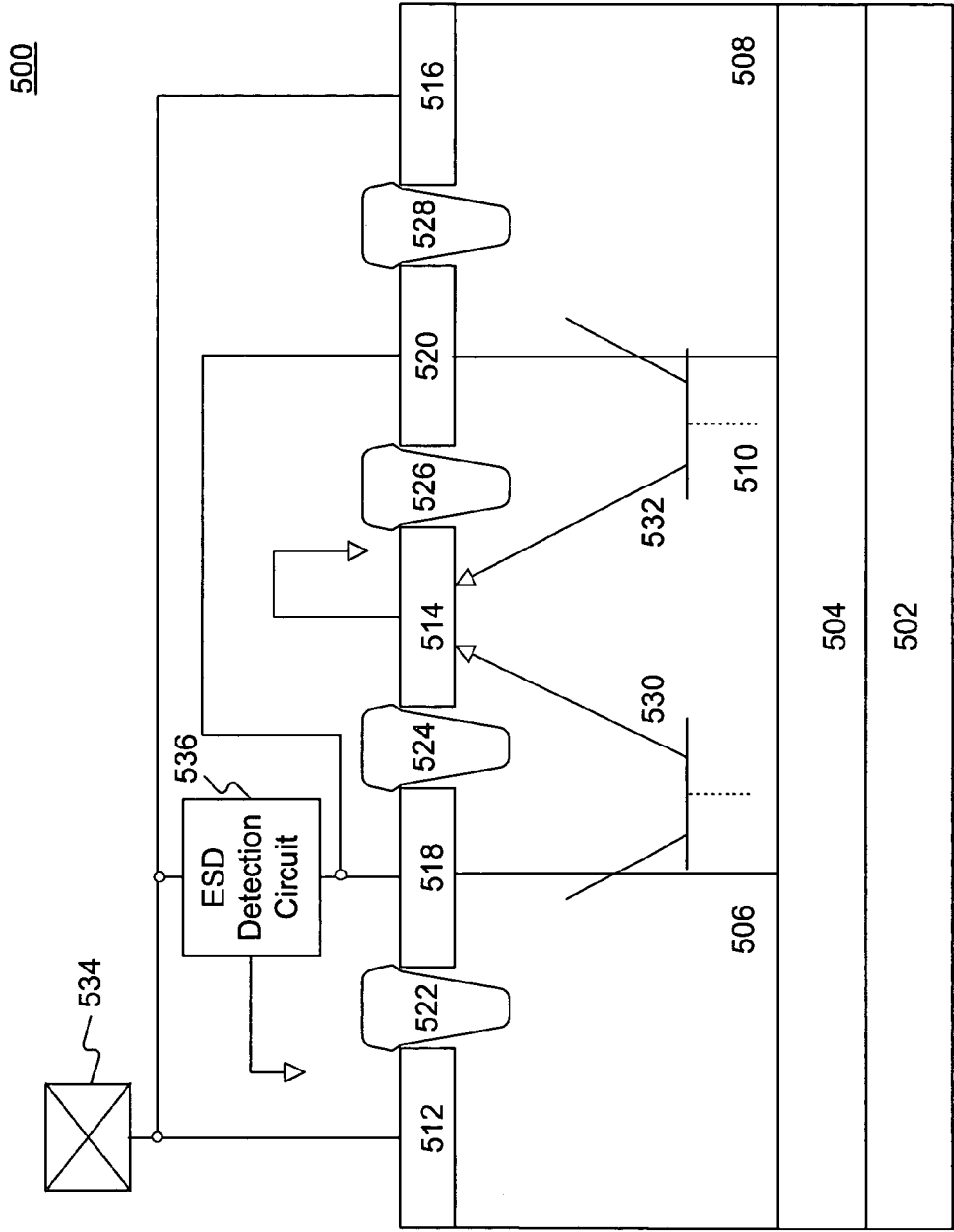
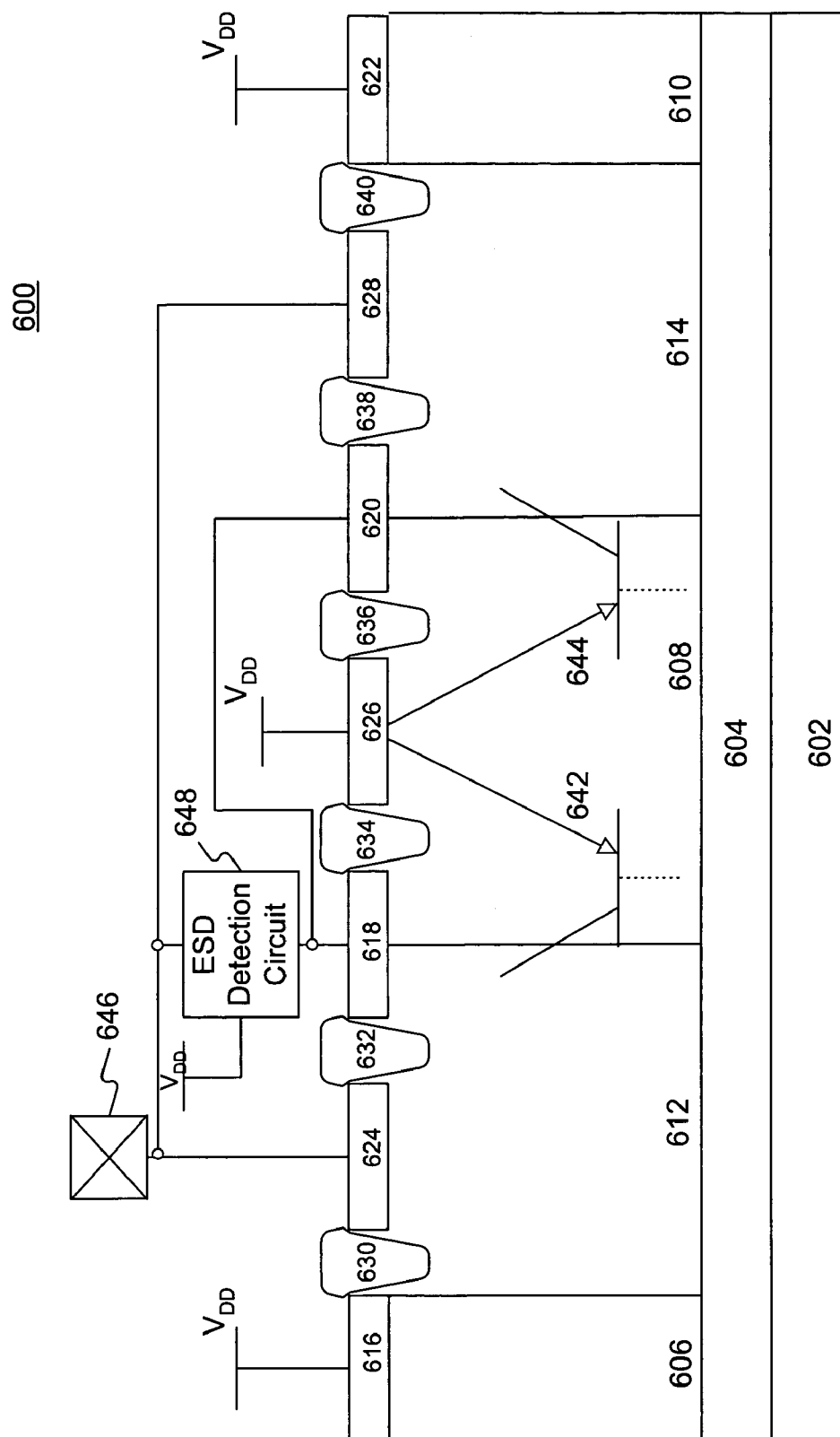


Fig. 7





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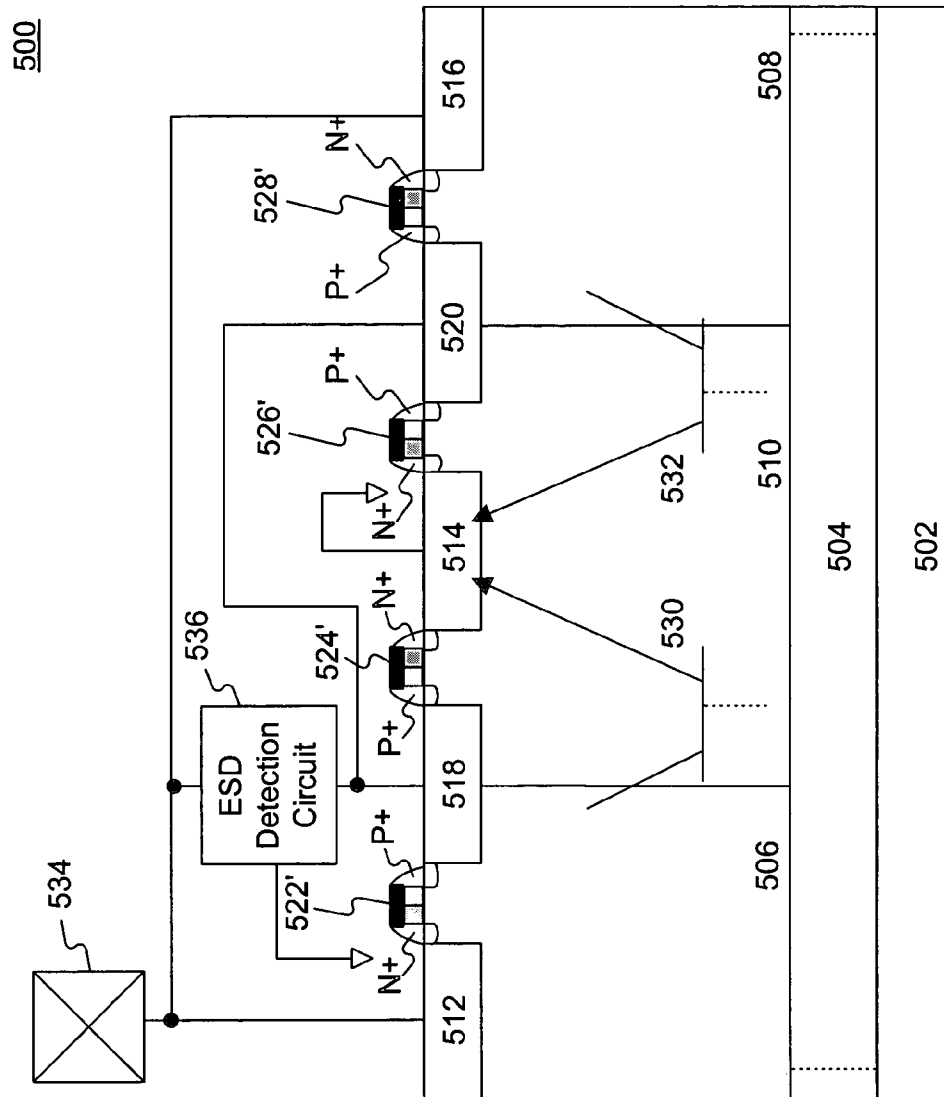
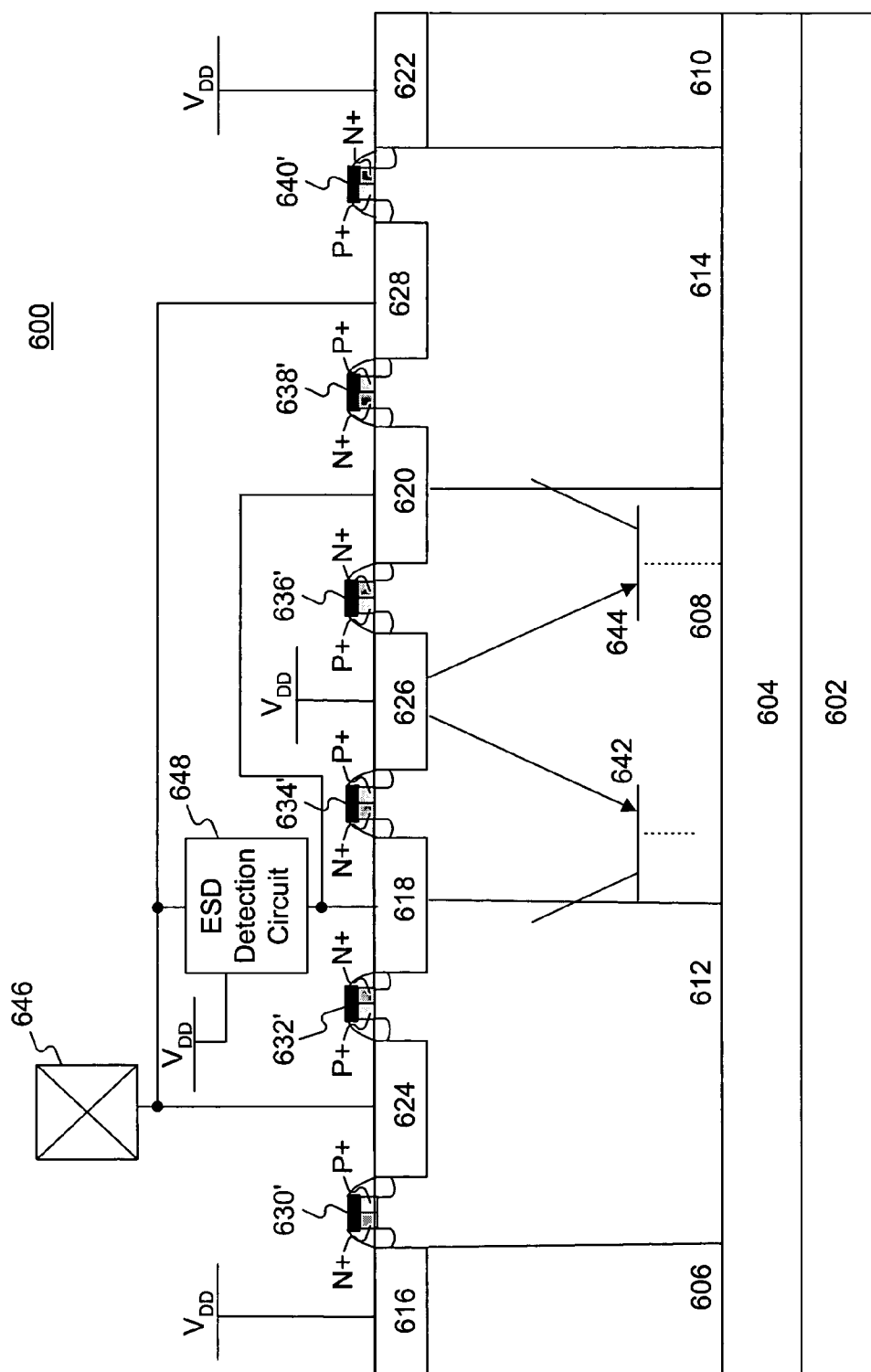


Fig. 9



**Fig. 10**

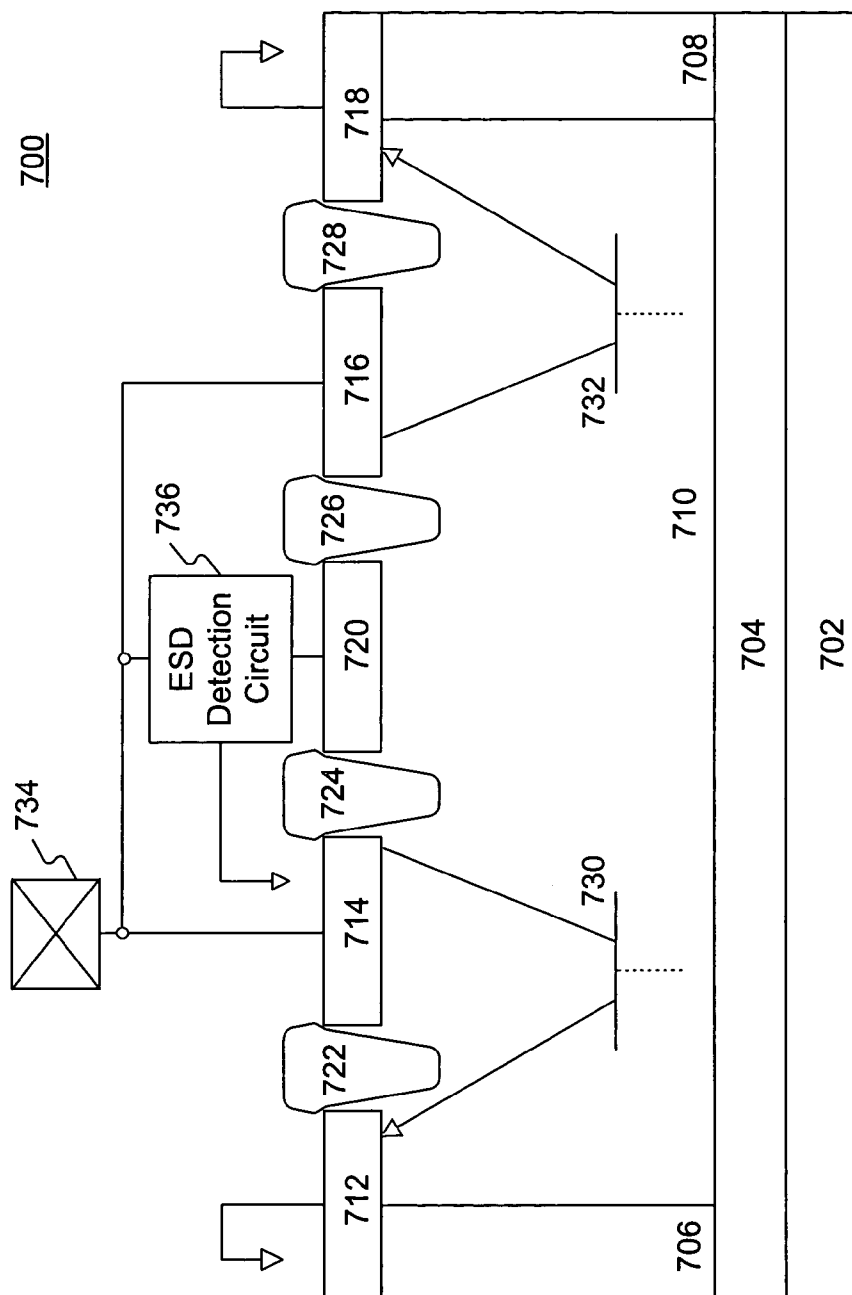


Fig. 11

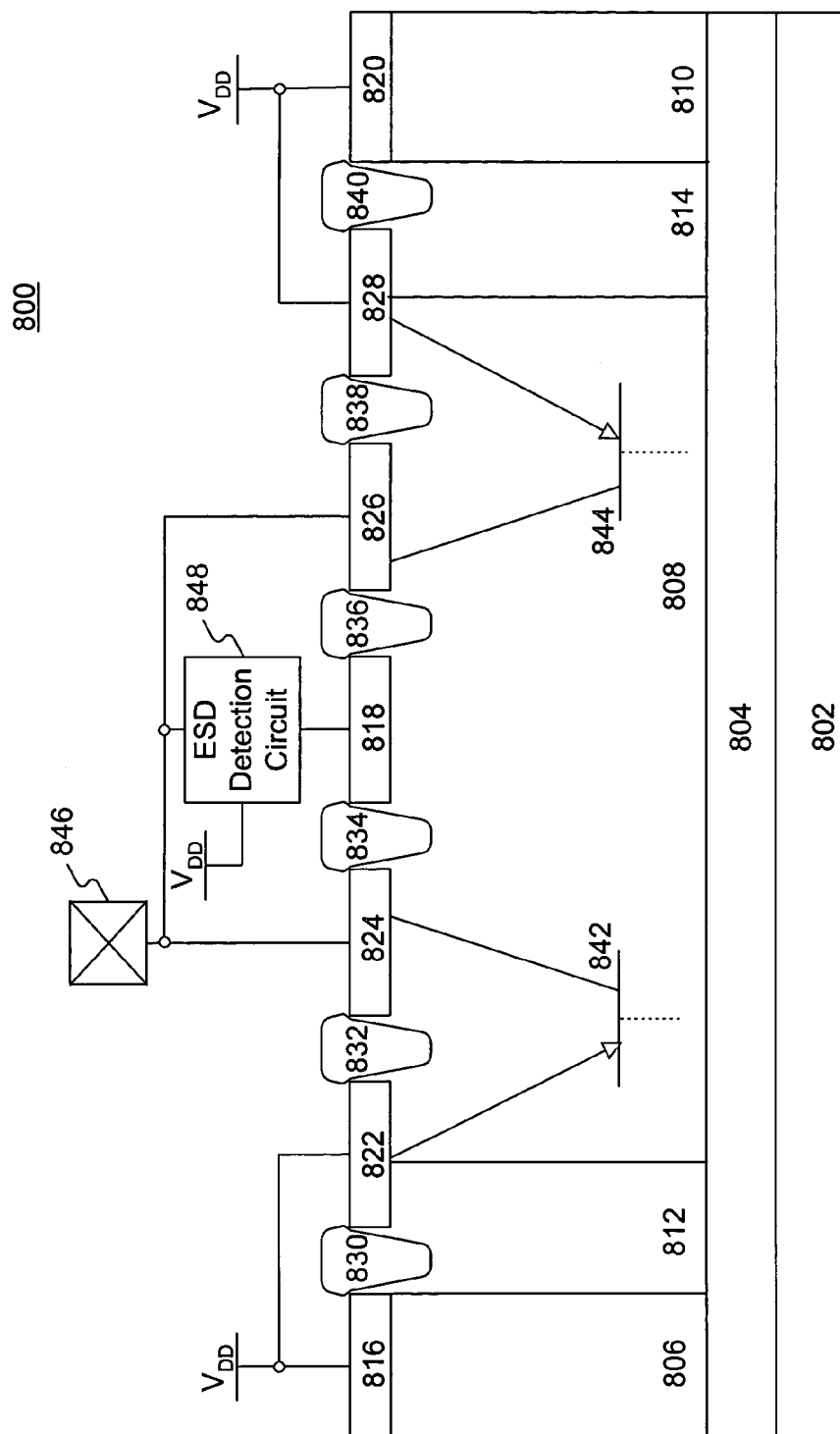


Fig. 12

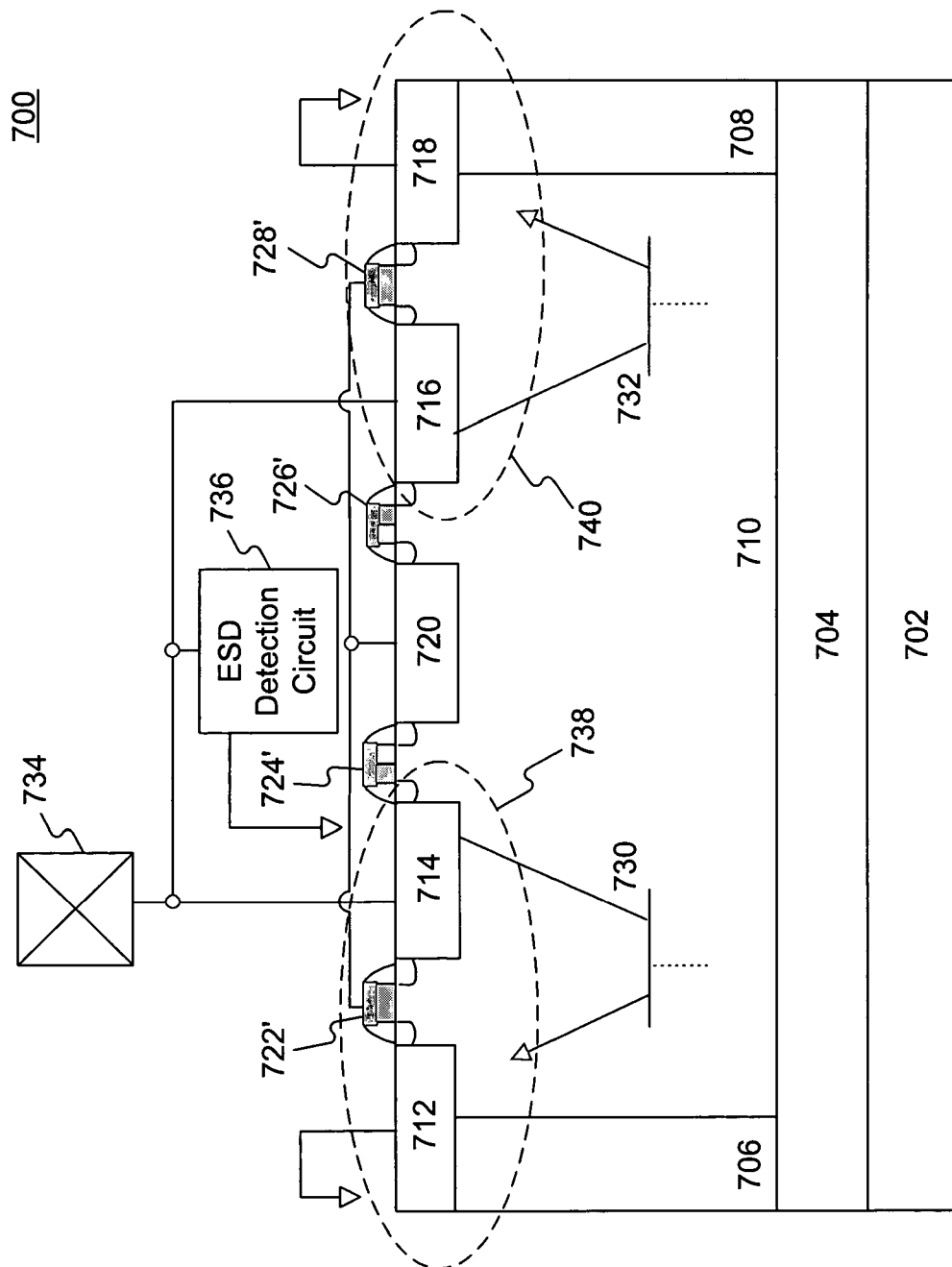


Fig. 13

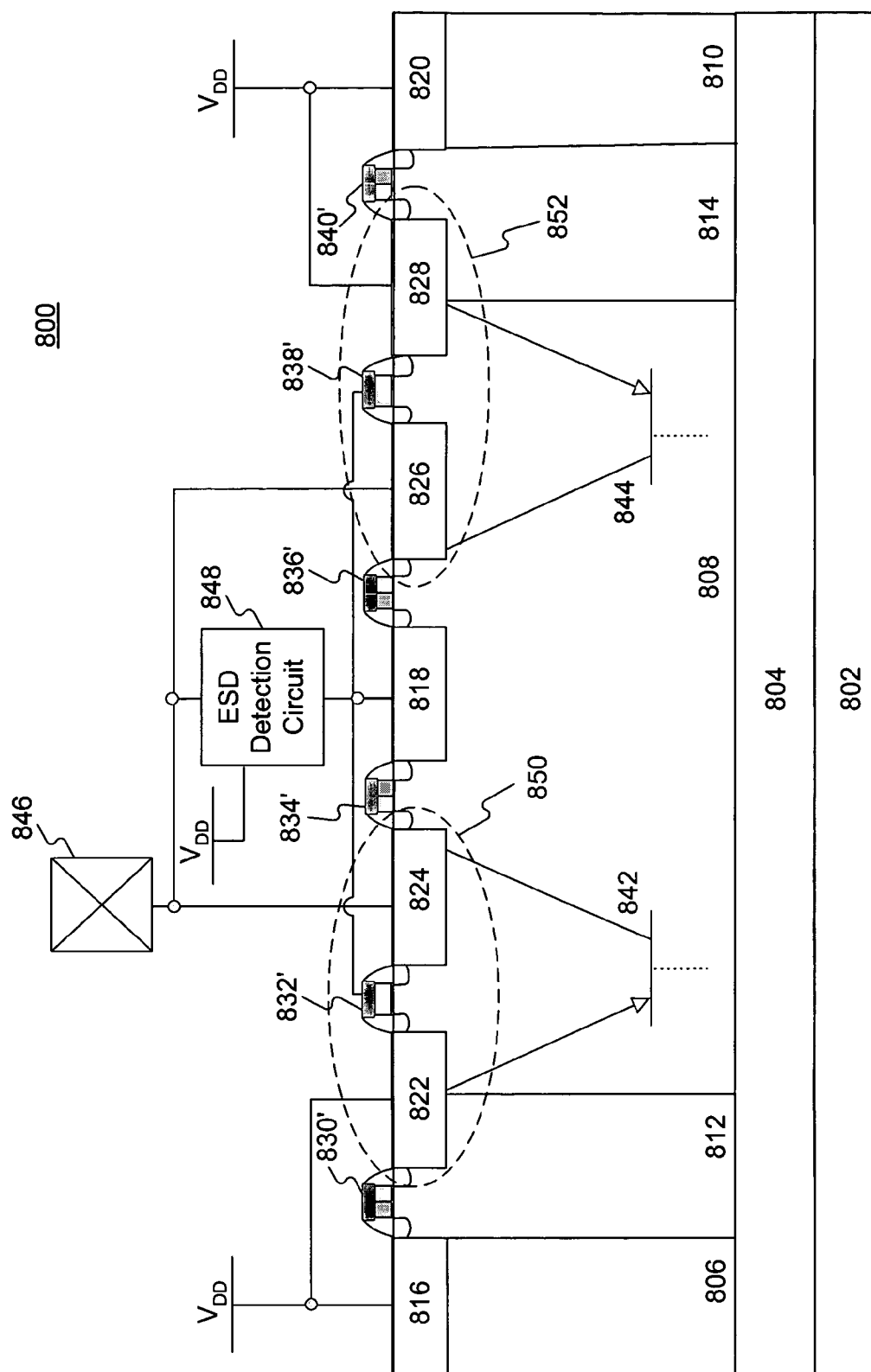


Fig. 14

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# TURN-ON-EFFICIENT BIPOLAR STRUCTURES WITH DEEP N-WELL FOR ON-CHIP ESD PROTECTION

## RELATED APPLICATION

The present application is related to, and claims the benefit of priority of, U.S. Provisional Application No. 60/487,581, filed on Jul. 17, 2003, entitled "Turn-on Efficient Bipolar Structure with Deep N-Well for On-Chip ESD Protection Design," which is incorporated herein by reference.

## DESCRIPTION OF THE INVENTION

### 1. Field of the Invention

This invention is related to semiconductor devices used for providing electrostatic discharge (ESD) protection and, more particularly, to semiconductor devices having bipolar structures for ESD protection.

### 2. Background of the Invention

A semiconductor integrated circuit (IC) is generally susceptible to an electrostatic discharge (ESD) event, which refers to a phenomenon of electrical discharge of a current (positive or negative) for a short duration during which a large amount of current is provided to the IC. An ESD event may damage or destroy the IC, and protection against the ESD is necessary for the IC. A conventional scheme for ESD protection incorporates a substrate-triggered ESD protection device.

FIG. 1 shows an IC 10 that includes an ESD protection circuit 100 for protecting IC 10 against ESD events. FIG. 2 is the cross-sectional view of ESD protection circuit 100. As shown in FIG. 1, IC 10 includes a contact pad 12 coupled to an internal circuit 14 through a driver circuit 16. Driver circuit 16 comprises a PMOS transistor 18 and an NMOS transistor 20. Each of PMOS transistor 18 and NMOS transistors 20 includes a source, a drain, and a gate. The source of PMOS transistor 18 is coupled to a positive power supply  $V_{DD}$ . The source of NMOS transistor 20 is coupled to ground or a negative power supply  $V_{SS}$ . Both the gates of PMOS transistor 18 and NMOS transistor 20 are coupled to contact pad 12. Both the drains of PMOS transistor 18 and NMOS transistor 20 are coupled to internal circuit 14.

ESD protection circuit 100 is coupled to contact pad 12 to detect an ESD event and protect IC 10 against the ESD. As shown in FIG. 1, ESD protection circuit 100 comprises NMOS transistors 102 and 104 and a resistor 106. Each of NMOS transistors 102 and 104 includes a substrate, a source, a drain, and a gate. The source of NMOS transistor 102 and the substrates of both NMOS transistors 102 and 104 are all coupled to one another, and are further coupled to one end of resistor 106. The gates of both NMOS transistors 102 and 104, the source of NMOS transistor 104, and the other end of resistor 106 are all coupled to  $V_{SS}$ . The drains of NMOS transistors 102 and 104 are both coupled to contact pad 12 and driver circuit 16.

Also shown in FIG. 1 is a bipolar junction transistor (BJT) 108 parasitic to NMOS transistor 104, wherein the substrate of NMOS transistor 104 is the base of BJT 108, and the source and the drain of NMOS transistor 104 are the emitter and collector of BJT 108.

In operation, when a positive ESD appears on contact pad 12, a positive potential appears on the drain of NMOS transistor 102, creating a high reverse bias across the junction between the drain and the substrate of NMOS transistor 102. The reverse bias across the drain-substrate junction of

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NMOS transistor 102 generates a current through ion implantation, which flows through the substrate of NMOS transistor 102 and resistor 106. As a result, the potential at the substrate of NMOS transistor 104, or the base of BJT 108, is increased, the base-emitter junction of BJT 108 is forward-biased, and BJT 108 is turned on to conduct the ESD to ground  $V_{SS}$ .

FIG. 2 is the cross-sectional view of an ESD protection circuit 200 manufactured in a p-type semiconductor substrate 202. ESD protection circuit 200 includes two ESD protection circuits 100 for protecting IC 10 against an ESD event. Each ESD protection circuit 100 includes NMOS transistors 102 and 104 and resistor 106, wherein each of NMOS transistors 104 includes a parasitic BJT 108. Semiconductor substrate 202 includes n-wells 204, 206, and 208, formed spaced apart from one another. The drain (not numbered) of one of NMOS transistors 108 is formed in n-well 204, the drain (not numbered) of the other NMOS transistor 108 is formed in n-well 208, and portions of the drains (not numbered) of both NMOS transistors 102 are formed in n-well 206. As indicated by the dashed lines in FIG. 2, resistors 106 are realized as the parasitic resistance of semiconductor substrate 202.

In addition, semiconductor substrate 202 has formed therein a plurality of diffusion regions, including P<sup>+</sup> regions 210, 212, 214, 216, and an N<sup>+</sup> region 218. P<sup>+</sup> regions 210 and 212 are formed in substrate 202 and isolated from n-wells 204 and 208 by shallow trench insulations (STIs) 220 and 222, respectively. P<sup>+</sup> regions 214 and 216 are formed in substrate 202, and each of P<sup>+</sup> regions 214 and 216 is adjacent to the source of a respective one of NMOS transistors 102. P<sup>+</sup> region 214 is isolated from the source of one of the NMOS transistors 104 by STI 224, and P<sup>+</sup> region 216 is isolated from the source of the other NMOS transistors 104 by STI 226. N<sup>+</sup> region 218 is formed in n-well 206 and isolated from the drains of NMOS transistors 102 by STIs 228 and 230.

Referring to FIG. 2, contact pad 12 is coupled to the drains of NMOS transistor 104, and also coupled to the drains of NMOS transistors 102 through N<sup>+</sup> region 218 and n-well 206. The gates of NMOS transistors 102 and 104, the sources of NMOS transistors 104, and P<sup>+</sup> regions 210 and 212 are all coupled to ground, or  $V_{SS}$ .

In an ESD event, the ESD is received at N<sup>+</sup> region 218 and is coupled to the drain of NMOS transistors 102 through n-well 206. A current due to ion implantation is generated through NMOS transistors 102, and flows to ground  $V_{SS}$  through resistors 106 and P<sup>+</sup> regions 210 and 212. As a result, the potential at the bases of BJTs 108 is increased to positive with respect to the emitters of BJTs 108. BJTs 108 are thus turned on to conduct the ESD to ground. Because the current through substrate 202, resistors 106, and P<sup>+</sup> regions 210 and 212 triggers BJTs 108 to conduct the ESD, the current is also referred to as a trigger current.

## SUMMARY OF THE INVENTION

In accordance with the present invention, there is provided a semiconductor device suitable for applications in an electrostatic discharge (ESD) protection circuit, including a semiconductor substrate, a first well formed in the substrate, a second well formed in the substrate, and a first doped region formed in the second well, wherein the first well, the second well, and the first doped region collectively form a parasitic bipolar junction transistor (BJT), and wherein the



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first well is the collector of the BJT, the second well is the base of the BJT, and the first doped region is the emitter of the BJT.

Also in accordance with the present invention, there is provided a semiconductor device suitable for applications in an electrostatic discharge (ESD) protection circuit, including a semiconductor substrate, a first well formed in the substrate, a second well formed in the substrate, a third well formed in the substrate, and a first doped region formed in the second well, wherein the first well, the second well, and the first doped region collectively form a first parasitic bipolar junction transistor (BJT), and wherein the second well, the third well, and the first doped region collectively form a second parasitic BJT, and wherein the first well is the collector of the first BJT, the third well is the collector of the second BJT, the second well is the base of both of the first and the second BJTs, and the first doped region is the emitter of both of the first and the second BJTs.

Further in accordance with the present invention, there is provided a semiconductor device suitable for applications in an electrostatic discharge (ESD) protection circuit, including a semiconductor substrate, a first well formed in the substrate, a second well formed in the substrate, a third well formed in the substrate, a first doped region formed in the second well, and a second doped region formed in the second well, wherein the first well, the second well, and the first doped region collectively form a first parasitic bipolar junction transistor (BJT), and the second well, the third well, and the second doped region collectively form a second parasitic BJT, and wherein the first well is the emitter of the first BJT, the third well is the emitter of the second BJT, the second well is the base of both of the first and the second BJTs, the first doped region is the collector of the first BJT, and the second doped region is the collector of the second BJT.

Still in accordance with the present invention, there is provided a method of providing electrostatic discharge (ESD) protections, including providing a semiconductor substrate, providing a first well in the substrate, providing a second well in the substrate, providing a first doped region in the second well, providing a second doped region in the substrate for receiving an ESD in an ESD event, wherein the second doped region is a contact to the first well, providing a third doped region in the substrate, and providing an ESD detection circuit for detecting the ESD, wherein the first well, the second well, and the first doped region are configured to form a parasitic bipolar junction transistor (BJT), and wherein the ESD detection circuit provides a trigger current or trigger voltage to the third doped region, which triggers the BJT to discharge the ESD.

Still further in accordance with the present invention, there is provided a method of providing electrostatic discharge (ESD) protections, including providing a semiconductor substrate, providing a first parasitic bipolar junction transistor (BJT) in the substrate, wherein the first BJT has an emitter, a collector, and a base, wherein the collector of the first BJT is coupled to receive an ESD in an ESD event, providing a second BJT in the substrate, wherein the second BJT has an emitter, a collector, and a base, wherein the collector of the BJT is coupled to receive the ESD, and providing an ESD detection circuit for detecting the ESD, wherein the ESD detection circuit provides a trigger current or trigger voltage in the ESD event to turn on the first BJT and the second BJT to discharge the ESD, wherein a well formed in the substrate is the base of both the first BJT and the second BJT, and the first BJT and the second BJT are triggered in the ESD event by the trigger current flowing through the well.

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Additional objects and advantages of the invention will be set forth in part in the description which follows, and in part will be obvious from the description, or may be learned by practice of the invention. The objects and advantages of the invention will be realized and attained by means of the elements and combinations particularly pointed out in the appended claims.

It is to be understood that both the foregoing general description and the following detailed description are exemplary and explanatory only and are not restrictive of the invention, as claimed.

#### BRIEF DESCRIPTION OF THE DRAWINGS

The accompanying drawings, which are incorporated in and constitute a part of this specification, illustrate embodiments of the invention and, together with the description, serve to explain the objects, advantages, and principles of the invention.

In the drawings,

FIG. 1 is a circuit diagram of a conventional electrostatic discharge (ESD) protection circuit;

FIG. 2 is the cross-sectional view of the ESD protection circuit shown in FIG. 1;

FIG. 3 is the cross-sectional view of a bipolar device suitable for providing ESD protections consistent with one embodiment of the present invention;

FIG. 4 is the cross-sectional view of a bipolar device suitable for providing ESD protections consistent with another embodiment of the present invention;

FIG. 5 is the cross-sectional view of another bipolar device suitable for providing ESD protections also consistent with the embodiment shown in FIG. 3;

FIG. 6 is the cross-sectional view of another bipolar device suitable for providing ESD protections also consistent with the embodiment shown in FIG. 4;

FIG. 7 is the cross-sectional view of a bipolar device suitable for providing ESD protections consistent with yet another embodiment of the present invention;

FIG. 8 is the cross-sectional view of a bipolar device suitable for providing ESD protections consistent still another embodiment of the present invention;

FIG. 9 is the cross-sectional view of another bipolar device suitable for providing ESD protections also consistent with the embodiment shown in FIG. 7;

FIG. 10 is the cross-sectional view of another bipolar device suitable for providing ESD protections also consistent with the embodiment shown in FIG. 8;

FIG. 11 is the cross-sectional view of a bipolar device suitable for providing ESD protections consistent with still yet another embodiment of the present invention;

FIG. 12 is the cross-sectional view of a bipolar device suitable for providing ESD protections consistent with yet another embodiment of the present invention;

FIG. 13 is the cross-sectional view of another bipolar device suitable for providing ESD protections also consistent with the embodiment shown in FIG. 11; and

FIG. 14 is the cross-sectional view of another bipolar device suitable for providing ESD protections also consistent with the embodiment shown in FIG. 12.

#### DESCRIPTION OF THE EMBODIMENTS

FIG. 3 is the cross-sectional view a substrate-triggered bipolar device 300 consistent with one embodiment of the present invention. Referring to FIG. 3, bipolar device 300 includes a substrate 302. Substrate 302 includes a plurality

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of N-wells 304, 306, and 308, and a P-well 310, wherein N-well 304 is formed deep in substrate 302 and isolates substrate 302 from N-wells 306 and 308 and P-well 310. P-well 310 is formed adjacent to N-well 306, and N-well 308 is formed adjacent to P-well 310. Also formed in substrate 302 are a plurality of diffusion regions, including N<sup>+</sup> regions 312, 314, and 316, and P<sup>+</sup> regions 318 and 320, wherein N<sup>+</sup> region 312 is formed in N-well 306, N<sup>+</sup> region 314 is formed in P-well 310, N<sup>+</sup> region 316 is formed in N-well 308, and P<sup>+</sup> region 320 is formed in P-well 310. P<sup>+</sup> region 318 is formed in both N-well 306 and P-well 310, i.e., a portion of P<sup>+</sup> region 318 is formed in N-well 306, and another portion of P<sup>+</sup> region 316 is formed in P-well 310. Hereinafter, when a diffusion region is described as having one portion formed in a first well and another portion formed in a second well, the diffusion region is described as having been formed in both the first well and the second well.

Diffusion regions 312, 314, 316, 318, and 320 are electrically isolated from each other by a plurality of isolation regions 322, 324, 326, and 328. Isolation region 322 electrically isolates N<sup>+</sup> region 312 from P<sup>+</sup> region 318; isolation region 324 electrically isolates P<sup>+</sup> region 318 from N<sup>+</sup> region 314; isolation region 326 electrically isolates N<sup>+</sup> region 314 from P<sup>+</sup> region 320; and isolation region 328 electrically isolates P<sup>+</sup> region 320 from N<sup>+</sup> region 316. In one aspect, isolation regions 322, 324, 326, and 328 are shallow trench isolations (STIs). In another aspect, isolation regions 322, 324, 326, and 328 are local oxidation of silicon (LOCOS) regions.

Also shown in FIG. 3 is a parasitic NPN bipolar junction transistor (BJT) 330 formed collectively by N-well 306, P-well 310, and N<sup>+</sup> region 314, wherein N-well 306 is the collector of BJT 330, P-well 310 is the base of BJT 330, and N<sup>+</sup> region 314 is the emitter of BJT 330. N<sup>+</sup> region 312 is the contact to N-well 306, or the collector of BJT 330, and P<sup>+</sup> region 318 is a contact to P-well 310, or the base of BJT 330. P<sup>+</sup> region 320 is also a contact to P-well 310, but is spaced apart from P<sup>+</sup> region 318.

In an exemplary application of bipolar device 300, N<sup>+</sup> region 312 is coupled to a contact pad 332 to receive an electrostatic discharge (ESD) current in an ESD event, and N<sup>+</sup> region 314 and P<sup>+</sup> region 320 are both grounded. An ESD detection circuit 334 is coupled between contact pad 332 and P<sup>+</sup> region 318 to detect the ESD. One terminal (not numbered) of ESD detection circuit 334 is grounded. N<sup>+</sup> region 316 is also coupled to contact pad 332. ESD detection circuit 334 may be implemented with any known ESD detection scheme and the details of which will not be described herein.

For illustration purposes, in the following descriptions of the embodiments of the present application, an ESD current flowing from the contact pad, such as contact pad 332, into the bipolar device, such as 300, is referred to as a positive ESD current, and an ESD current flowing from the bipolar device to the contact pad is referred to as a negative ESD current.

In operation, when a positive ESD current is received at contact pad 332, ESD detection circuit 334 detects the ESD and provides a trigger current to P<sup>+</sup> region 318. The trigger current flows through P-well 310 to P<sup>+</sup> region 320. The trigger current generates a positive potential due to the non-zero parasitic resistance of P-well 310 from P<sup>+</sup> region 318 to P<sup>+</sup> region 320 and triggers, or turns on, BJT 330 to conduct the positive ESD current from N<sup>+</sup> region 312 to N<sup>+</sup> region 314, which, in turn, is coupled to ground.

Referring again to FIG. 3, since a portion of P<sup>+</sup> region 318 is formed in N-well 306, N-well 306 and N<sup>+</sup> region 314 are formed close to each other. As a result, the effective base

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width of BJT 330, which is approximately the distance between N-well 306 and N<sup>+</sup> region 314, is reduced to a minimum. Therefore, the gain of BJT 330 is increased and a turn-on speed of BJT 330 is improved.

As discussed above, bipolar device 300 as shown in FIG. 3 includes an NPN BJT for discharging an ESD. According to another embodiment of the present invention, there is also provided a substrate-triggered bipolar device including a PNP BJT suitable for providing ESD protection. FIG. 4 shows the cross-sectional view of such a bipolar device 400 consistent with the second embodiment of the present invention.

Referring to FIG. 4, bipolar device 400 includes a substrate 402. A plurality of N-wells 404, 406, and 408, and a P-well 410 are formed in substrate 402, wherein N-well 404 is formed deep in substrate 402 and isolates substrate 402 from N-wells 406 and 408 and P-well 410. P-well 410 is formed adjacent to N-well 406, and N-well 408 is formed adjacent to P-well 410. Also formed in substrate 402 are a plurality of diffusion regions, including N<sup>+</sup> regions 412, 414, and 416, and P<sup>+</sup> regions 418 and 420, wherein N<sup>+</sup> region 412 is formed in N-well 406, N<sup>+</sup> region 416 is formed in N-well 408, P<sup>+</sup> region 418 is formed in P-well 410, P<sup>+</sup> region 420 is formed in N-well 408, and N<sup>+</sup> region 414 is formed in both N-well 408 and P-well 410.

Diffusion regions 412, 414, 416, 418, and 420 are electrically isolated from each other by a plurality of isolation regions 422, 424, 426, and 428. Isolation region 422 electrically isolates N<sup>+</sup> region 412 from P<sup>+</sup> region 418; isolation region 424 electrically isolates P<sup>+</sup> region 418 from N<sup>+</sup> region 414; isolation region 426 electrically isolates N<sup>+</sup> region 414 from P<sup>+</sup> region 420; and isolation region 428 electrically isolates P<sup>+</sup> region 420 from P<sup>+</sup> region 416. In one aspect, isolation regions 422, 424, 426, and 428 are STIs. In another aspect, isolation regions 422, 424, 426, and 428 are LOCOS.

P-well 410, N-well 408, and P<sup>+</sup> region 420 collectively form a parasitic PNP BJT 430, wherein P-well 410 is the collector of BJT 430, N-well 408 is the base of BJT 430, and P<sup>+</sup> region 420 is the emitter of BJT 430. P<sup>+</sup> region 418 is the contact to P-well 410, or the collector of BJT 430, and N<sup>+</sup> region 414 is a contact to N-well 408, or the base of BJT 430. N<sup>+</sup> region 416 is also a contact to N-well 408, but is spaced apart from N<sup>+</sup> region 414.

In an exemplary application of bipolar device 400, P<sup>+</sup> region 418 is coupled to a contact pad 432 to receive an ESD current in an ESD event, and N<sup>+</sup> regions 412 and 416 and P<sup>+</sup> region 420 are all connected to a positive power supply VDD. An ESD detection circuit 434 is coupled between contact pad 432 and N<sup>+</sup> region 414 to detect the ESD. A terminal of ESD detection circuit 434 is also connected to V<sub>DD</sub>.

In an ESD event, when a negative ESD current appears on contact pad 432, ESD detection circuit 434 detects the ESD and generates a trigger current from N<sup>+</sup> region 414. The trigger current flows through N-well 408 from N<sup>+</sup> region 416, which is connected to V<sub>DD</sub>, to N<sup>+</sup> region 414. Because of the non-zero parasitic resistance of N-well 408, the potential near N<sup>+</sup> region 414 is lowered to a relative negative value with respect to V<sub>DD</sub>. As a result, BJT 430 is triggered, or turned on, to conduct the negative ESD current from P<sup>+</sup> region 418 to P<sup>+</sup> region 420, which, in turn, is connected to positive power supply V<sub>DD</sub>.

In one aspect, since a portion of N<sup>+</sup> region 414 is formed in P-well 410, P-well 410 and P<sup>+</sup> region 420 are formed close to each other. In other words, the effective base width of BJT 430 is very small and, therefore, the turn-on speed of BJT 430 is improved.

Also according to the present invention, the isolation regions in the first and second embodiments described above may be replaced with dummy gates, thereby further reducing the dimension of the bipolar device. FIGS. 5 and 6 respectively show the realization of bipolar devices 300 and 400 with dummy gates.

Referring to FIG. 5, isolation regions 322, 324, 326, and 328 of bipolar device 300 are replaced with dummy gate structures 322', 324', 326', and 328', respectively, without modifying the remaining structures. Referring to FIG. 6, isolation regions 422, 424, 426, and 428 of bipolar device 400 are replaced with dummy gate structures 422', 424', 426', and 428', respectively, without modifying the remaining structures. As shown in FIGS. 5 and 6, the gates of these dummy gate structures are doped with both P<sup>+</sup> and N<sup>+</sup> dopants, wherein a portion of the gates proximate a P<sup>+</sup> region is doped with P<sup>+</sup> dopant, and a portion of the gates proximate an N<sup>+</sup> region is doped with N<sup>+</sup> dopant. Because a dummy gate has a substantially smaller size than an STI or LOCOS isolation, the configurations as shown in FIGS. 5 and 6 need a substantially smaller chip area than those show in FIGS. 3 and 4.

According to the present invention, there is also provided a floating-base bipolar device suitable for providing ESD protection. FIG. 7 shows a floating-base bipolar device 500 including parasitic NPN BJTs consistent with a third embodiment of the present invention.

Referring to FIG. 7, bipolar device 500 is formed in a semiconductor substrate 502. A plurality of N-wells 504, 506, and 508, and a P-well 510 are formed in substrate 502, wherein N-well 504 is formed deep in substrate 502 and isolates substrate 502 from N-wells 506 and 508 and P-well 510. P-well 510 is formed adjacent to N-well 506, and N-well 508 is formed adjacent to P-well 510. A plurality of diffusion regions, including N<sup>+</sup> regions 512, 514, and 516, and P<sup>+</sup> regions 518 and 520 are formed in substrate 502, wherein N<sup>+</sup> region 512 is formed in N-well 506, N<sup>+</sup> region 514 is formed in P-well 510, N<sup>+</sup> region 516 is formed in N-well 508, P<sup>+</sup> region 518 is formed in both N-well 506 and P-well 510, and P<sup>+</sup> region 520 is formed in both P-well 510 and N-well 508.

Diffusion regions 512, 514, 516, 518, and 520 are electrically isolated from each other by a plurality of isolation regions 522, 524, 526, and 528. Isolation region 522 electrically isolates N<sup>+</sup> region 512 from P<sup>+</sup> region 518; isolation region 524 electrically isolates P<sup>+</sup> region 518 from N<sup>+</sup> region 514; isolation region 526 electrically isolates N<sup>+</sup> region 514 from P<sup>+</sup> region 520; and isolation region 528 electrically isolates P<sup>+</sup> region 520 from N<sup>+</sup> region 516. In one aspect, isolation regions 522, 524, 526, and 528 are STIs. In another aspect, isolation regions 522, 524, 526, and 528 are LOCOS.

As shown in FIG. 7, N-well 506, P-well 510, and N<sup>+</sup> region 514 collectively form a parasitic NPN BJT 530, and N-well 508, P-well 510, and N<sup>+</sup> region 516 collectively form a parasitic NPN BJT 532, wherein N-well 506 is the collector of BJT 530, N-well 508 is the collector of BJT 532, P-well 510 is the base of both BJT 530 and BJT 532, and N<sup>+</sup> region 514 is the emitter of both BJT 530 and BJT 532.

In an exemplary application of bipolar device 500, N<sup>+</sup> regions 512 and 516 are both coupled to a contact pad 534 to receive an ESD current in an ESD event, and N<sup>+</sup> region 514 is grounded. An ESD detection circuit 536 is coupled to contact pad 534 to detect the ESD, and both P<sup>+</sup> regions 518 and 520 are coupled to ESD detection circuit 536. A terminal (not numbered) of ESD detection circuit 536 is also grounded.

In the event that a positive ESD current appears on contact pad 534, ESD detection circuit 536 detects the ESD and generates a trigger current or a trigger voltage at P<sup>+</sup> regions 518 and 520 to turn on BJTs 530 and 532 to conduct the positive ESD current from N<sup>+</sup> regions 512 and 516 to N<sup>+</sup> region 514.

Consistent with a fourth embodiment of the present invention, there is also provided a floating-base bipolar device 600 including PNP BJTs for providing ESD protections. Referring to FIG. 8, bipolar device 600 is formed in a semiconductor substrate 602. A plurality of N-wells 604, 606, 608, and 610, and two P-wells 612 and 614 are formed in substrate 602, wherein N-well 604 is formed deep in substrate 602 and isolates substrate 602 from N-wells 606, 608, and 610 and P-wells 612 and 614. P-well 612 is formed adjacent to N-well 606, N-well 608 is formed adjacent to P-well 612, P-well 614 is formed adjacent to N-well 608, and N-well 610 is formed adjacent to P-well 614. A plurality of diffusion regions, including N<sup>+</sup> regions 616, 618, 620, and 622, and P<sup>+</sup> regions 624, 626, and 628 are also formed in substrate 602, wherein N<sup>+</sup> region 616 is formed in N-well 606, N<sup>+</sup> region 618 is formed in both P-well 612 and N-well 608, N<sup>+</sup> region 620 is formed in both N-well 608 and P-well 614, N<sup>+</sup> region 622 is formed in N-well 610, P<sup>+</sup> region 624 is formed in P-well 612, P<sup>+</sup> region 626 is formed in N-well 608, and P<sup>+</sup> region 628 is formed in P-well 614.

Diffusion regions 616, 618, 620, 622, 624, 626, and 628 are electrically isolated from each other by a plurality of isolation regions 630, 632, 634, 636, 638, and 640. Isolation region 630 electrically isolates N<sup>+</sup> region 616 from P<sup>+</sup> region 624; isolation region 632 electrically isolates P<sup>+</sup> region 624 from N<sup>+</sup> region 618; isolation region 634 electrically isolates N<sup>+</sup> region 618 from P<sup>+</sup> region 626; isolation region 636 electrically isolates P<sup>+</sup> region 626 from N<sup>+</sup> region 620; isolation region 638 electrically isolates N<sup>+</sup> region 620 from P<sup>+</sup> region 628; and isolation region 640 electrically isolates P<sup>+</sup> region 628 from N<sup>+</sup> region 622. In one aspect, isolation regions 630, 632, 634, 636, 638, and 640 are STIs. In another aspect, isolation regions 630, 632, 634, 636, 638, and 640 are LOCOS.

As shown in FIG. 8, P-well 612, N-well 608, and P<sup>+</sup> region 626 collectively form a parasitic PNP BJT 642, and P-well 614, N-well 608, and P<sup>+</sup> region 626 collectively form a parasitic PNP BJT 644, wherein P-well 612 is the collector of BJT 642, P-well 614 is the collector of BJT 644, N-well 608 is the base of both BJT 642 and BJT 644, and P<sup>+</sup> region 626 is the emitter of both BJT 642 and BJT 644.

In an exemplary application of bipolar device 600, N<sup>+</sup> regions 616 and 622 and P<sup>+</sup> region 626 are all connected to a positive power supply V<sub>DD</sub>. P<sup>+</sup> regions 624 and 628 are both coupled to a contact pad 646 to receive an ESD in an ESD event. An ESD detection circuit 648 is coupled to contact pad 646 to detect the ESD, and both N<sup>+</sup> regions 618 and 620 are coupled to ESD detection circuit 648. A terminal (not numbered) of ESD detection circuit 648 is also connected to V<sub>DD</sub>.

When a negative ESD current appears on contact pad 646, ESD detection circuit 648 detects the ESD and generates a trigger current or a trigger voltage at N<sup>+</sup> regions 618 and 620 to turn on BJTs 642 and 644 to conduct the negative ESD current from P<sup>+</sup> regions 624 and 628 to P<sup>+</sup> region 626, which, in turn, is coupled to a positive power supply.

Similarly, the isolation regions in the third and fourth embodiments may also be replaced with dummy gates to further reduce the dimension of the bipolar devices. FIGS. 9 and 10 respectively show the realization of bipolar devices 500 and 600 with dummy gates. Referring to FIG. 9,

isolation regions **522**, **524**, **526**, **528** of bipolar device **500** have been replaced with dummy gate structures **522'**, **524'**, **526'**, **528'**, respectively, without modifying the remaining structures. Referring to FIG. **10**, isolation regions **630**, **632**, **634**, **636**, **638**, and **640** of bipolar device **600** have been replaced with dummy gate structures **630'**, **632'**, **634'**, **636'**, **638'**, and **640'**, respectively, without modifying the rest of the structure. The gates of these dummy gate structures are doped with both P<sup>+</sup> and N<sup>+</sup> dopants, wherein a portion of the gates proximate a P<sup>+</sup> region is doped with P<sup>+</sup> dopant, and a portion of the gates proximate an N<sup>+</sup> region is doped with N<sup>+</sup> dopant, as shown in both FIGS. **9** and **10**.

Accord to the present invention, there is also provided a bipolar device for providing ESD protection, wherein the bipolar device has a large area for heat dissipation, and therefore device stability is improved. FIG. **11** shows a bipolar device **700** including NPN BJTs that have a large area for heat dissipation consistent with a fifth embodiment of the present invention. Referring to FIG. **11**, bipolar device **700** is formed in a semiconductor substrate **702**. A plurality of N-wells **704**, **706**, and **708**, and a P-well **710** are formed in substrate **702**, wherein N-well **704** is formed deep in substrate **702** and separates substrate **702** from N-wells **706** and **708** and P-well **710**. P-well **710** is formed adjacent to N-well **706**, and N-well **708** is formed adjacent to P-well **710**.

Also formed in substrate **702** are a plurality of diffusion regions, including N<sup>+</sup> regions **712**, **714**, **716**, and **718**, and a P<sup>+</sup> region **720**, wherein N<sup>+</sup> region **712** is formed in both N-well **706** and P-well **710**, N<sup>+</sup> regions **714** and **716** are formed in P-well **710**, N<sup>+</sup> region **718** is formed in both N-well **708** and P-well **710**, and P<sup>+</sup> region **720** is formed in P-well **710**. Diffusion regions **712**, **714**, **716**, **718**, and **720** are electrically isolated from each other by a plurality of isolation regions **722**, **724**, **726**, and **728**. Isolation region **722** electrically isolates N<sup>+</sup> region **712** from N<sup>+</sup> region **714**; isolation region **724** electrically isolates N<sup>+</sup> region **714** from P<sup>+</sup> region **720**; isolation region **726** electrically isolates P<sup>+</sup> region **720** from N<sup>+</sup> regions **716**; and isolation region **728** electrically isolates N<sup>+</sup> region **716** from N<sup>+</sup> region **718**. In one aspect, isolation regions **722**, **724**, **726**, and **728** are STIs. In another aspect, isolation regions **722**, **724**, **726**, and **728** are LOCOS.

N<sup>+</sup> region **714**, P-well **710**, and N-well **706** collectively form a parasitic NPN BJT **730**, and N<sup>+</sup> region **716**, P-well **710**, and N<sup>+</sup> region **718** collectively form a parasitic NPN BJT **732**, wherein N<sup>+</sup> region **714** is the collector of BJT **730**, N<sup>+</sup> region **716** is the collector of BJT **732**, P-well **710** is the base of both BJTs **730** and **732**, N-well **706** is the emitter of BJT **730**, and N-well **708** is the emitter of BJT **732**. N<sup>+</sup> region **712** is the contact to N-well **706**, and N<sup>+</sup> region **718** is the contact to N-well **708**.

In an exemplary application of bipolar device **700**, N<sup>+</sup> regions **712** and **718** are grounded. N<sup>+</sup> regions **714** and **716** are coupled to a contact pad **734** to receive an ESD current in an ESD event. An ESD detection circuit **736** is coupled between contact pad **734** and P<sup>+</sup> region **720** to detect the ESD. A terminal (not numbered) of ESD detection circuit **736** is also grounded. When a positive ESD current appears on contact pad **734**, ESD detection circuit **736** detects the ESD and generates a trigger current or a trigger voltage at P<sup>+</sup> region **720**, thereby turning on BJTs **730** and **732** to conduct the ESD from N<sup>+</sup> regions **714** and **716** to N<sup>+</sup> regions **712** and **718**, respectively.

As shown in FIG. **11**, the emitters of BJTs **730** and **732** are N-wells **706** and **708**, different from FIG. **7**, which shows the emitter of BJTs **530** and **532** as N<sup>+</sup> region **514**. Therefore, the

heat dissipation area of BJTs **730** and **732** is much larger compared to that of BJTs **530** and **532**. Consequently, the stability of the device is improved.

FIG. **12** shows a bipolar device **800** including PNP BJTs that have large heat dissipation areas consistent with a sixth embodiment of the present invention. Referring to FIG. **12**, bipolar device **800** is formed in a semiconductor substrate **802**. A plurality of N-wells **804**, **806**, **808**, and **810**, and two P-wells **812** and **814** are formed in substrate **802**, wherein N-well **804** is formed deep in substrate **802** and isolates substrate **802** from N-wells **806**, **808**, and **810**, and P-wells **812** and **814**. P-well **812** is formed adjacent to N-well **806**, N-well **808** is formed adjacent to P-well **812**, P-well **814** is formed adjacent to N-well **808**, and N-well **810** is formed adjacent to P-well **814**. Also formed in substrate **802** are a plurality of diffusion regions, including N<sup>+</sup> regions **816**, **818**, and **820**, and P<sup>+</sup> regions **822**, **824**, **826**, and **828**, wherein N<sup>+</sup> region **816** is formed in N-well **806**, N<sup>+</sup> region **818** is formed in N-well **808**, N<sup>+</sup> region **820** is formed in N-well **810**, P<sup>+</sup> region **822** is formed in both P-well **812** and N-well **808**, P<sup>+</sup> regions **824** and **826** are both formed in N-well **808**, and P<sup>+</sup> region **828** is formed in both N-well **808** and P-well **814**.

Diffusion regions **816**, **818**, **820**, **822**, **824**, **826**, and **828** are electrically isolated by a plurality of isolation regions **830**, **832**, **834**, **836**, **838**, and **840**. Isolation region **830** electrically isolates N<sup>+</sup> region **816** from P<sup>+</sup> region **822**; isolation region **832** electrically isolates P<sup>+</sup> region **822** from P<sup>+</sup> region **824**; isolation region **834** electrically isolates P<sup>+</sup> region **824** from N<sup>+</sup> region **818**; isolation region **836** electrically isolates N<sup>+</sup> region **818** from P<sup>+</sup> region **826**; isolation region **838** electrically isolates P<sup>+</sup> region **826** from P<sup>+</sup> region **828**; and isolation region **840** electrically isolates P<sup>+</sup> region **828** from N<sup>+</sup> region **820**. In one aspect, isolation regions **830**, **832**, **834**, **836**, **838**, and **840** are STIs. In another aspect, isolation regions **830**, **832**, **834**, **836**, **838**, and **840** are LOCOS.

As shown in FIG. **12**, P<sup>+</sup> region **824**, N-well **808**, and P-well **812** collectively form a parasitic PNP BJT **842**, and P<sup>+</sup> regions **826**, N-well **808**, and P-well **814** collectively form a parasitic PNP BJT **844**, wherein P<sup>+</sup> region **824** is the collector of BJT **842**, P<sup>+</sup> region **826** is the collector of BJT **844**, N-well **808** is the base of both BJTs **842** and **844**, P-well **812** is the emitter of BJT **842**, and P-well **814** is the emitter of BJT **844**.

In an exemplary application of bipolar device **800**, N<sup>+</sup> regions **816** and **820**, and P<sup>+</sup> regions **822** and **828** are all connected to a positive power supply  $V_{DD}$ . P<sup>+</sup> regions **824** and **826** are both coupled to a contact pad **846** to receive an ESD current in an ESD event. An ESD detection circuit **848** is coupled between contact pad **846** and N<sup>+</sup> region **818** to detect the ESD. A terminal (not numbered) of ESD detection circuit **848** is also connected to  $V_{DD}$ .

When a negative ESD current appears on contact pad **846**, ESD detection circuit **848** detects the ESD and generates a trigger current or trigger voltage at N<sup>+</sup> region **818**, which then triggers or turns on BJTs **842** and **844** to conduct the negative ESD current from P<sup>+</sup> regions **824** and **826** to P<sup>+</sup> regions **822** and **828**, respectively.

For the reasons already discussed above, the structure of bipolar device **800** also provides for a better heat dissipation and therefore the stability thereof is improved.

Furthermore, the isolation regions in bipolar devices **700** and **800** may also be replaced with dummy gates. As shown in FIG. **13**, isolation regions **722**, **724**, **726**, and **728** of bipolar device **700** have been replaced with dummy gate structures **722'**, **724'**, **726'**, and **728'**, respectively, without modifying the remaining structures.

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In one aspect, the gate of each of the gate structures **724'** and **726'** is doped with both P<sup>+</sup> and N<sup>+</sup> dopants, while gate structures **722'** and **728'** are both doped with N<sup>+</sup> dopant. As indicated by the dashed circles in FIG. 13, two n-type MOS transistors **738** and **740** are formed, with N<sup>+</sup> regions **712** and **714** being the source and drain of MOS transistor **738**, N<sup>+</sup> regions **716** and **718** being the source and drain of MOS transistor **740**, and P-well **710** being the substrate of both NMOS transistors **738** and **740**. In one aspect, both of the gates of NMOS transistors **738** and **740**, i.e., gates **722'** and **728'**, are coupled to ESD detection circuit **736** to receive the trigger current or trigger voltage to trigger or turn on BJTs **730** and **732**. Therefore, BJTs **730** and **732** may be turned on more quickly.

Referring to FIG. 14, isolation regions **830**, **832**, **834**, **836**, **838**, and **840** have been replaced with dummy gate structures **830'**, **832'**, **834'**, **836'**, **838'**, and **840'**, respectively, without modifying the remaining structures. In one aspect, the gate of each of the gate structures **830'**, **834'**, **836'**, and **840'** is doped with both P<sup>+</sup> and N<sup>+</sup> dopants, while gate structures **832'** and **838'** are both doped with N<sup>+</sup> dopant. As indicated by the dashed circles in FIG. 14, two p-type MOS transistors **850** and **852** are formed, wherein P<sup>+</sup> regions **822** and **824** are the source and drain of MOS transistor **850**, P<sup>+</sup> regions **826** and **828** are the source and drain of MOS transistor **852**, and N-well **808** is the substrate of both NMOS transistors **850** and **852**. In one aspect, both of the gates of NMOS transistors **850** and **852**, i.e., gates **832'** and **838'**, are coupled to ESD detection circuit **848** to receive the trigger current or trigger voltage, thereby triggering or turning on BJTs **842** and **844**. Therefore, BJTs **842** and **844** may be turned on more quickly.

It will be apparent to those skilled in the art that various modifications and variations can be made in the disclosed process without departing from the scope or spirit of the invention. Other embodiments of the invention will be apparent to those skilled in the art from consideration of the specification and practice of the invention disclosed herein. It is intended that the specification and examples be considered as exemplary only, with a true scope and spirit of the invention being indicated by the following claims.

What is claimed is:

1. A semiconductor device, comprising:
  - a semiconductor substrate;
  - a first well formed in the substrate;
  - a second well formed in the substrate;
  - a first doped region formed in the second well,
  - a second doped region formed in both the first well and the second well; and
  - a deep well formed in the substrate that physically isolates the substrate from at least the second well,
 wherein the first well, the second well, and the first doped region collectively form a parasitic bipolar junction transistor (BJT),
 wherein the first well comprises a collector of the BJT, the second well comprises a base of the BJT, the first doped region comprises an emitter of the BJT, and wherein the second doped region is adapted to receive a trigger current or a trigger voltage.
2. The semiconductor device of claim 1, wherein the first well comprises an n-type well, the second well comprises a p-type well, the first doped region comprises an n-type region, and the parasitic BJT comprises an NPN BJT.
3. The semiconductor device of claim 2, wherein the deep well comprises an n-type well.
4. The semiconductor device of claim 1, wherein the first well comprises a p-type well, the second well comprises an

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n-type well, the first doped region comprises a p-type region, and the parasitic BJT comprises a PNP BJT.

5. The semiconductor device of claim 1, further comprising:

a third doped region formed in the substrate, wherein the second doped region and the first well comprise a same type of conductivity, and the second doped region comprises a contact to the first well, and wherein the third doped region and the second well comprise a same type of conductivity, and the third doped region comprises a contact to the second well.

6. The semiconductor device of claim 5, further comprising an ESD detection circuit,

wherein the first doped region is connectable to a power supply,

wherein the second doped region is connectable to a contact pad for receiving an ESD current, and wherein the third doped region is connectable to the ESD detection circuit coupled to the contact pad for detecting the ESD current.

7. The semiconductor device of claim 6, wherein the ESD detection circuit is adapted to provide a trigger current to the third doped region in an ESD event, and

wherein in response to the trigger current the parasitic BJT is adapted to conduct the ESD current from the second doped region to the first doped region or from the first doped region to the second doped region.

8. The semiconductor device of claim 6, wherein the BJT comprises an NPN BJT, and the power supply comprises ground.

9. The semiconductor device of claim 6, wherein the BJT comprises a PNP BJT, and the power supply comprises a positive supply voltage.

10. The semiconductor device of claim 6, further comprising a fourth doped region formed in the second well, wherein the fourth doped region and the second well comprise a same type of conductivity, wherein the fourth doped region comprises a contact to the second well, wherein the third doped region and the fourth doped region are spaced apart from each other, and wherein the fourth doped region is connectable to the power supply.

11. The semiconductor device of claim 1, further comprising

a third doped region formed in the substrate; and a fourth doped region formed in the second well, wherein the first, second, third, and fourth doped regions are electrically isolated from each other by a plurality of isolation regions.

12. The semiconductor device of claim 11, wherein the isolation regions comprise shallow trench isolations (STIs).

13. The semiconductor device of claim 11, wherein the isolation regions comprise oxidation of silicon (LOGOS) regions.

14. The semiconductor device of claim 1, further comprising

a third doped region formed in the substrate; and a fourth doped region formed in the second well, wherein the first, second, third, and fourth doped regions are electrically isolated from each other by a plurality of dummy gate structures.

15. The semiconductor device of claim 14, wherein the gates of the dummy gate structures are doped with both P<sup>+</sup> and N<sup>+</sup> dopants, wherein a portion of the gates proximate a p-type doped region is doped with P<sup>+</sup> dopant, and a portion of the gates proximate an n-type doped region is doped with N<sup>+</sup> dopant.

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16. The semiconductor device of claim 1, and wherein in response to the trigger current or the trigger voltage the BJT is adapted to discharge current in the ESD event.

17. The semiconductor device of claim 1, wherein the deep well further physically isolates the substrate from the first well.

18. A semiconductor device, comprising:

a semiconductor substrate;

a first well formed in the substrate;

a second well formed in the substrate; and

a third well formed in the substrate; and

a first doped region formed in the second well,

wherein the first well, the second well, and the first doped region collectively form a first parasitic bipolar junction transistor (BJT), and wherein the second well, the third well, and the first doped region collectively form a second parasitic BJT, and wherein the first well comprises a collector of the first BJT, the third well comprises a collector of the second BJT, the second well comprises a base of both of the first and the second BJTs, and the first doped region comprises an emitter of both of the first and the second BJTs.

19. The semiconductor device of claim 18, wherein the first BJT and the second BJT comprise NPN-BJTs.

20. The semiconductor device of claim 18, wherein the first BJT and the second BJT comprise PNP BJTs.

21. The semiconductor device of claim 18, further comprising

a second doped region formed in the first well;

a third doped region formed in the third well;

a fourth doped region formed in the substrate; and

a fifth doped region formed in the substrate,

wherein the second doped region and the first well comprise a same type of conductivity, and the second doped region comprises a contact to the first well,

wherein the third doped region and the third well comprise a same type of conductivity, and the third doped region comprises a contact to the third well, and

wherein the fourth doped region, the fifth doped region, and the second well comprise a same type of conductivity, wherein the fourth doped region and the fifth doped region comprise contacts to the second well, and wherein the fourth doped region and the fifth doped region are spaced apart from each other.

22. The semiconductor device of claim 21,

wherein the first doped region is connectable to a power supply,

wherein the second and the third doped regions are connectable to a contact pad for receiving an ESD current, and

wherein the fourth and fifth doped regions are connectable to an ESD detection circuit, wherein the ESD detection circuit is coupled to the contact pad for detecting the ESD current.

23. The semiconductor device of claim 22, wherein the ESD detection circuit is adapted to provide a trigger current or a trigger voltage to the fourth and fifth doped regions in an ESD event, wherein in response to the trigger current or trigger voltage provided to the fourth doped region the first BJT is adapted to conduct the ESD current from the second doped region to the first doped region or from the first doped region to the second doped region, and in response to the trigger current or trigger voltage provided to the fifth doped region the second BJT is adapted to conduct the ESD current from the third doped region to the first doped region or from the first doped region to the third doped region.

24. The semiconductor device of claim 21, wherein the first, second, third, fourth, and fifth doped regions are electrically isolated from each other.

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25. The semiconductor device of claim 21, further comprising a plurality of dummy gate structures to electrically isolate at least two of the first, second, third, fourth, and fifth doped regions.

26. The semiconductor device of claim 25, wherein the gates of the dummy gate structures are doped with both P<sup>+</sup> and N<sup>+</sup> dopants, wherein a portion of the gates proximate a p-type doped region is doped with P<sup>+</sup> dopant, and a portion of the gates proximate an n-type doped is doped with N<sup>+</sup> dopant.

27. The semiconductor device of claim 21, wherein a portion of the fourth doped region is formed in the first well, and another portion of the fourth doped region is formed in the second well, and wherein a portion of the fifth doped region is formed in the second well, and another portion of the fifth doped region is formed in the third well.

28. A semiconductor device, comprising:

a semiconductor substrate;

a first well formed in the substrate;

a second well formed in the substrate;

a third well formed in the substrate;

a deep well formed in the substrate that physically isolates the substrate from the first, second, and third wells;

a first doped region formed in the second well;

a second doped region formed in the second well,

a third doped region formed in both the first well and the second well;

a fourth doped region formed in the second well; and

a fifth doped region formed in both the second well and the third well,

wherein the first well, the second well, and the first doped region collectively form a first parasitic bipolar junction transistor (BJT), and the second well; the third well, and the second doped region collectively form a second parasitic BJT, and

wherein the first well comprises an emitter of the first BJT, the third well comprises an emitter of the second BJT, the second well comprises a base of both of the first and the second BJTs, the first doped region comprises a collector of the first BJT, and the second doped region comprises a collector of the second BJT.

29. The semiconductor device of claim 28, further comprising

wherein the third doped region comprises a contact to the first well;

wherein the fifth doped region comprises a contact to the third well, and

wherein the first and second doped regions are connectable to a contact pad, the third and fifth doped regions are connectable to a power supply, the fourth doped region is connectable to an ESD detection circuit, and the ESD detection circuit is coupled to the contact pad.

30. The semiconductor device of claim 29, wherein the ESD detection circuit is adapted to trigger the first and second BJTs to conduct current from the first and second doped regions to the third and fifth doped regions, respectively, or from the third and fifth regions to the first and second doped regions, respectively.

31. The semiconductor device of claim 29, wherein the first doped region, the second doped region, the third doped region, the fourth doped region, and the fifth doped region are isolated from each other by a plurality of gate structures, wherein a first gate structure is formed between the first and third doped regions, and the first gate structure, the first doped region, the third doped region, and the second well form a first MOS transistor, wherein a second gate structure is formed between the second and fifth doped regions, and the second gate structure, the second doped region, the fifth doped region, and the second well form a second MOS transistor.

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32. The semiconductor device of claim 31, wherein the first gate and the second gate are both connectable to the ESD detection circuit to trigger the first and second BJTs to discharge current in an ESD event.

33. The semiconductor device of claim 28, wherein the deep well comprises an n-type well.

34. An apparatus, comprising:

a first well formed in a semiconductor substrate;

a second well formed in the substrate adjacent to the first well, the second well of a different conductivity type than the first well;

a deep well formed in the substrate and physically isolating at least the first well from the substrate;

first and second doped regions formed at least partially in the first well and of the same conductivity type as the first well; and

a third doped region formed in the first well between the first and second doped regions, the third doped region of a different conductivity type than the first well,

wherein the first doped region is formed in both the first well and the second well, and

wherein the first doped region is adapted to receive a trigger current and/or a trigger voltage.

35. The apparatus of claim 34, wherein the first well comprises an p-well, the second well comprises an n-well, the deep well comprises an n-well, and the first doped region comprises an p-type doped region.

36. The apparatus of claim 35, further comprising:

a third well formed in the substrate adjacent to the first well and spaced apart from the second well, the third well of a same conductivity type as the second well, and

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wherein the second doped region is formed in both the first well and the third well.

37. The apparatus of claim 34, wherein the deep well further physically isolates the substrate from the first well.

38. The apparatus of claim 34, further comprising:

an electrostatic discharge (ESD) detection circuit coupled to the first doped region.

39. The apparatus of claim 34, wherein the first well comprises an n-well, the second well comprises a p-well, the deep well comprises an n-well, and the first doped region comprises an n-type doped region.

40. The apparatus of claim 34, further comprising:

a plurality of isolation regions adapted to electrically isolate the first, second, and third doped regions from each other.

41. The apparatus of claim 40, wherein the isolation regions comprise shallow trench isolations (STIs).

42. The apparatus of claim 40, wherein the isolation regions comprise oxidation of silicon (LOGOS) regions.

43. The apparatus of claim 40, wherein the isolation regions comprise dummy gate structures.

44. The apparatus of claim 34,

wherein the first well, the second well, and the third doped region comprise, respectively, a collector, a base, and an emitter of a parasitic bipolar junction transistor (BJT), and

wherein the parasitic BJT is adapted to discharge an electrostatic discharge (ESD) current in response to the trigger current or the trigger voltage.

\* \* \* \* \*